



First Named Inventor	Leonard Forbes
Serial No.	10/808,058
Filing Date	March 24, 2004
Group Art Unit	2818
Examiner Name	Unknown
Confirmation No.	4217
Attorney Docket No.	400.288US01

DPW

**GENERAL  
TRANSMITTAL  
FORM UNDER 37 CFR 1.8  
(LARGE ENTITY)**

Title: MEMORY DEVICE WITH HIGH DIELECTRIC CONSTANT GATE DIELECTRICS AND METAL FLOATING GATES

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Commissioner for Patents

P. O. Box 1450

Alexandria, VA 22313-1450

**Enclosures**

The following documents are enclosed:

Information Disclosure Statement (1 pg.); Form 1449 (7 pgs.); 58 copies of cited references; U.S. reference(s) not included pursuant to 37 C.F.R. 1.98 (c)(2)(i);  
 An itemized return-receipt postcard

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**Please charge any additional fees or credit any overpayments  
to Deposit Account No. 501373.**

**CUSTOMER NO. 27073**

**Submitted By**

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Signature	<i>Kenneth W. Bolvin</i>			Date	<i>9/2/04</i>

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I certify that this correspondence and the identified documents listed on this transmittal are being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Mail Stop: AMENDMENT, Commissioner for Patents, P. O. Box 1450, Alexandria, VA 22313-1450 on September 2, 2004.

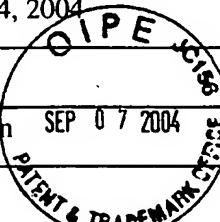
Name	Rhonda L. Foley	Signature	<i>Rhonda L. Foley</i>
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(LARGE ENTITY TRANSMITTAL UNDER 37 CFR § 1.8)

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INFORMATION  
DISCLOSURE  
STATEMENT



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In compliance with 37 C.F.R. §§ 1.56 and 1.97, *et seq.*, the enclosed materials are brought to the attention of the Examiner for consideration in connection with the above-identified Application.

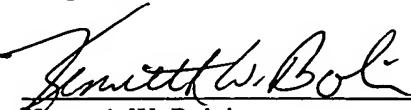
Pursuant to 37 C.F.R. 1.98 (a)(2)(i), as this application was filed after June 30, 2003, Applicant has not included copies of U.S. Patents or U.S. Patent Applications. Applicant respectfully requests that this Information Disclosure Statement be entered and the references listed on the attached Form 1449 be considered by the Examiner and made of record. Pursuant to MPEP §609, Applicant further requests that the Examiner initial next to each reference on the Form 1449 to indicate that the listed references have been considered. Applicant further requests that a copy of the initialed Form 1449 be returned with the next official communication.

As an Office Action has not yet issued in this application, Applicant believes that no fees are due. However, the Commissioner for Patents is hereby authorized to charge any additional fees to Deposit Account No. 501373.

If the Examiner has any questions or concerns regarding this application, please contact the undersigned at (612) 312-2211.

Respectfully submitted,

Date: 9/2/04

  
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Based on Form PTO-FB-A820 Patent and Trademark Office, U.S. Department of Commerce

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	Certified Translation, "Flash cell that seeks to replace current technology introduced enabling both low cost and high performance" Nikkei Microdevices, November 1999, pp. 147-148.

Examiner Signature		Date Considered	
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\*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.